ELECTRUM LAB
KTH & ACREO IN COLLABORATION

Electrum Laboratory

Complete Solutions in Nano and Microtechnology

Nils Nordell

(Director)

ELECTRUM LAB
KTH & ACREO IN COLLABORATION

Electrum Laboratory

Mission

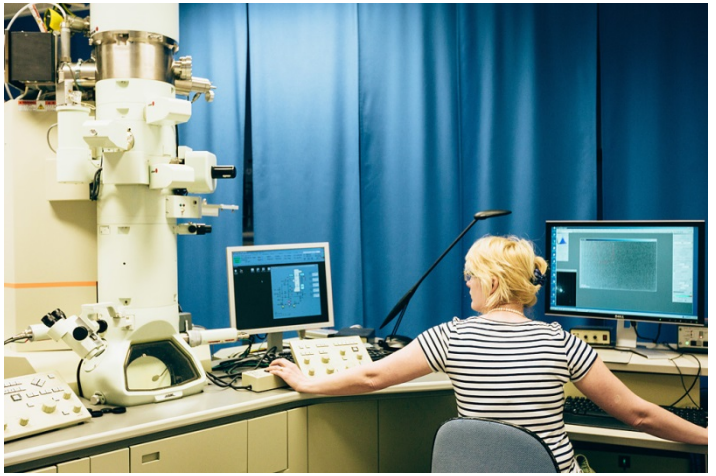
- To offer a competitive laboratory environment for micro and nano technology:
  - Processes capabilities – including cleanroom – for device fabrication
  - Facilities for characterization of materials and devices.
- To create an open environment for education, research, development and small scale production.
- To assure a cost efficient usage of expensive laboratory resources.

A flexible lab resource

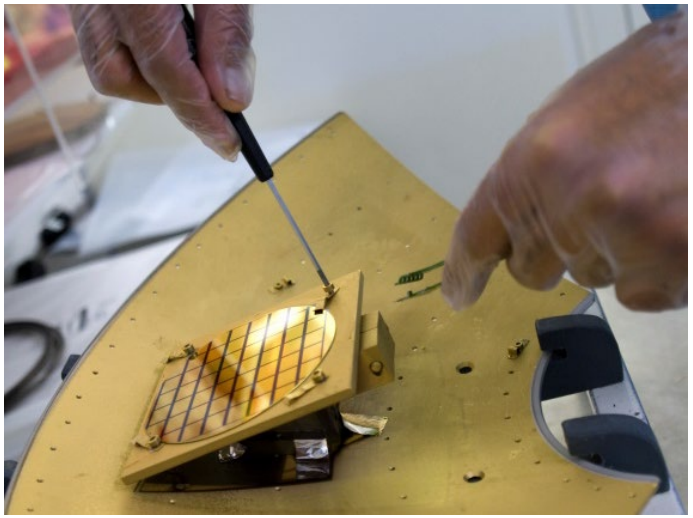
- **Research and development**
  - Inventing, designing, manufacturing of novel devices
  - Establishing novel processes and characterization techniques
  - Synthesis and characterization of new materials and structures
  - Flexibility, allowing different materials and sizes

- **Small scale production**
  - Incubator for start-up and spin-off companies
  - Access to all the lab resources
  - Possibility to rent lab space for proprietary equipment
  - Stability and repeatability maintained

- **Education**
  - Advanced graduate and undergraduate courses.
  - Micro- and nano fabrication technologies and characterization.



Open Access Laboratory Facilities



Open for academic and commercial users.

Easy access to processing and characterization tools.

Education for lab access and tool driving licenses.

Tool expert assistance or driving license.

Rent of lab space

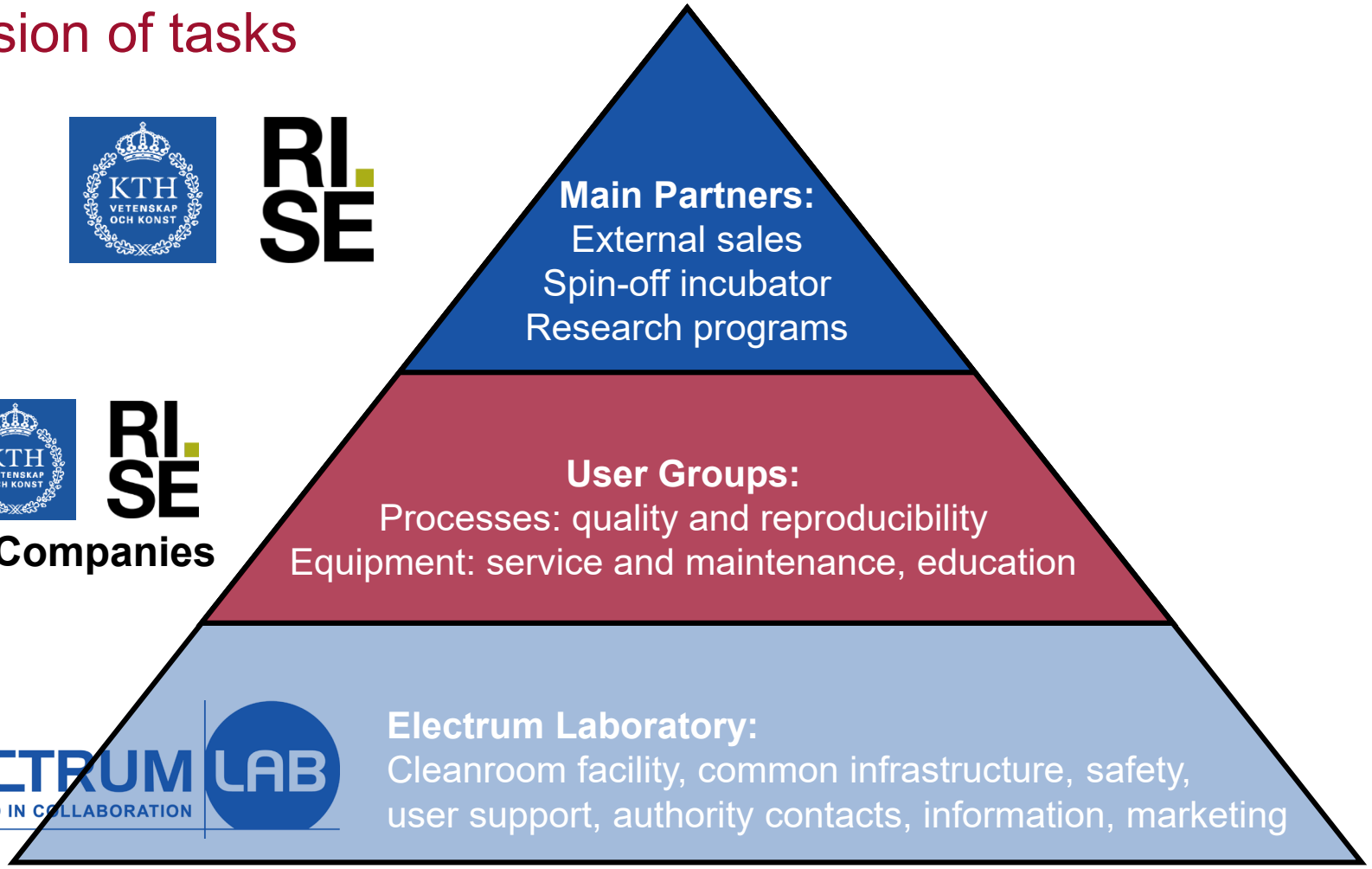
Possibilities for research collaborations.

Simple business model:
- Pay per user and use
- Myfab one-stop shop solution

Common user interface through MyfabLIMS:
- Databases of tools and users
- Booking, Logging, Invoicing

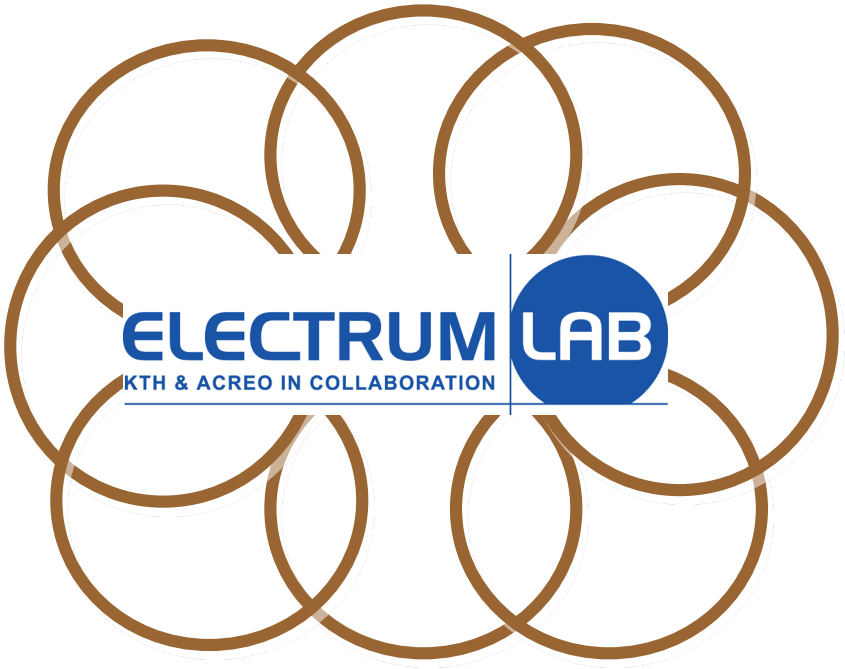
Electrum Lab organization

- Division of tasks



Electrum Lab organization

- Involving the user groups



Lab Director has a coordinating role.

Major user groups are represented in the Management team and Task forces handling:

- Lab organization and rules
- Quality management
- Lab safety
- Tool investments
- Facility planning
- Cross contamination and tool rules
- Fee system

Tool Investments and responsibility

Tool investments funded by:

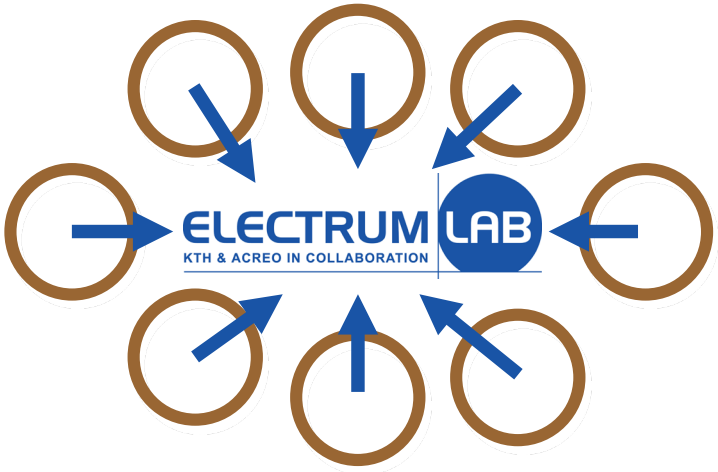
- Research grants - private and governmental
- User groups - some open for general use
- Electrum Lab - user fees or grants

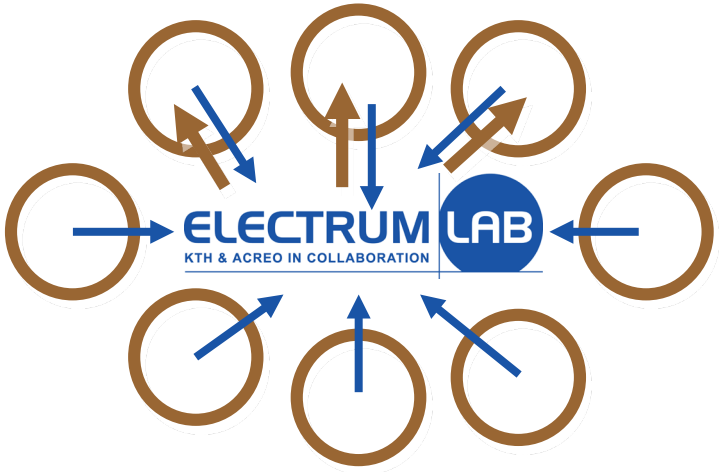
Tool and process responsibility:

- On the user groups
- Handle maintenance, service, consumables, process control etc.
- Not always the owner of the tool
- Encouraged to sell tool time
- May be canceled at any time
- ➢ ***Certify access to key processes***

Economic control

- Charges and reimbursement





Lab fees are paid to Electrum lab for basic infrastructure, premises, coordination etc.

Fees based on:

- Registered users
- Hours in cleanroom
- Lab area (for tool responsible)

Tool fees are paid to Electrum lab and reimbursed to tool responsible groups for consumables, maintenance, lab area, etc.

Fees based on:

- Used tool time

Fees are differentiated: Academic / Micro companies & Institutes / Large companies

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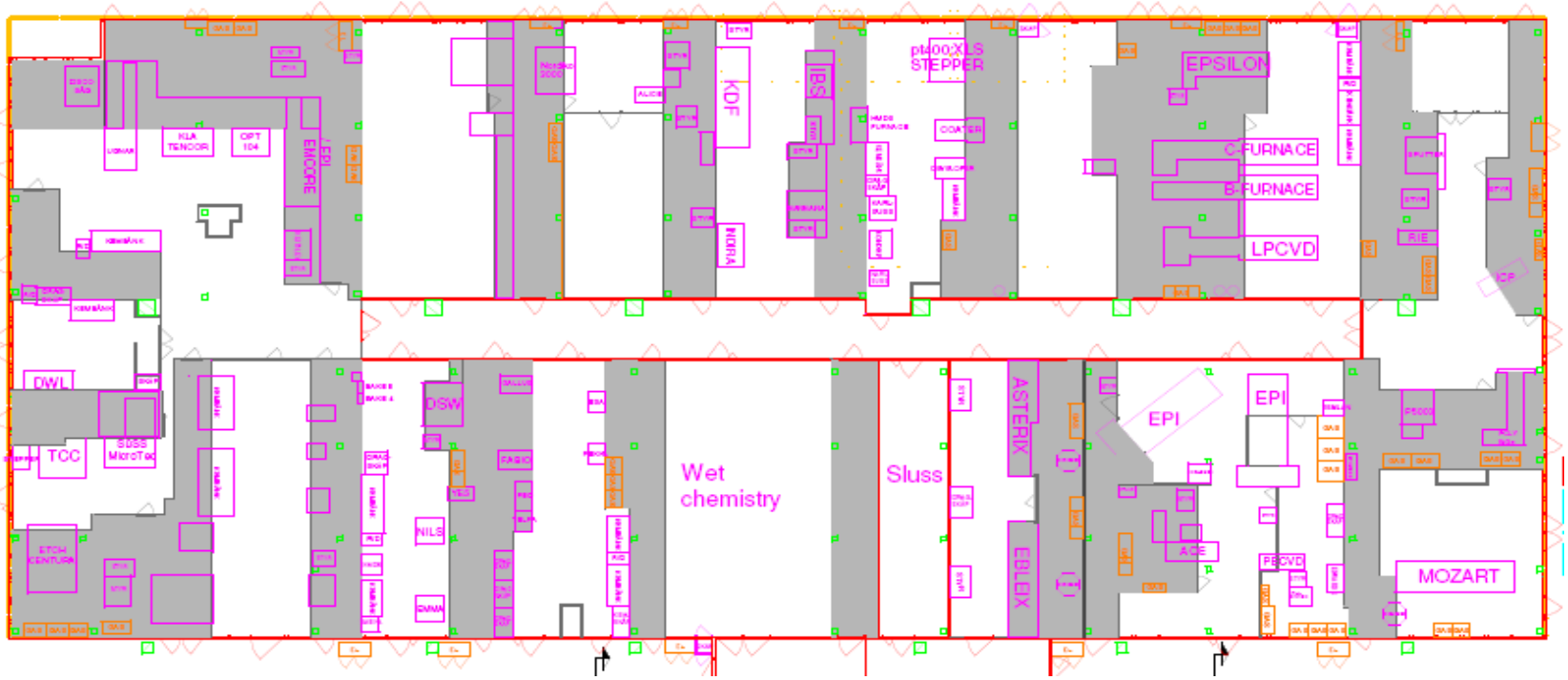
Key Figures



In operation since 1987

1 300 m^2 clean room lab
Class 100 - 10 000 (particles/ft^3)
1 500 m^2 other labs

Yearly turn around: 55 MSEK

No. users: c:a 250
No. dependent of lab: > 600

Total investment value: > 800 MSEK
No. registered tools: 220
Average tool lifetime: 15 years
Re-investment: 15 MSEK/yr

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Process Lines

ISO 9001 certified management system

- *controlled processes and tool uptime*
- *calibrated characterization tools:*

Silicon Technology

Silicon - CMOS
Silicon - Microsystems

Compound Semiconductors

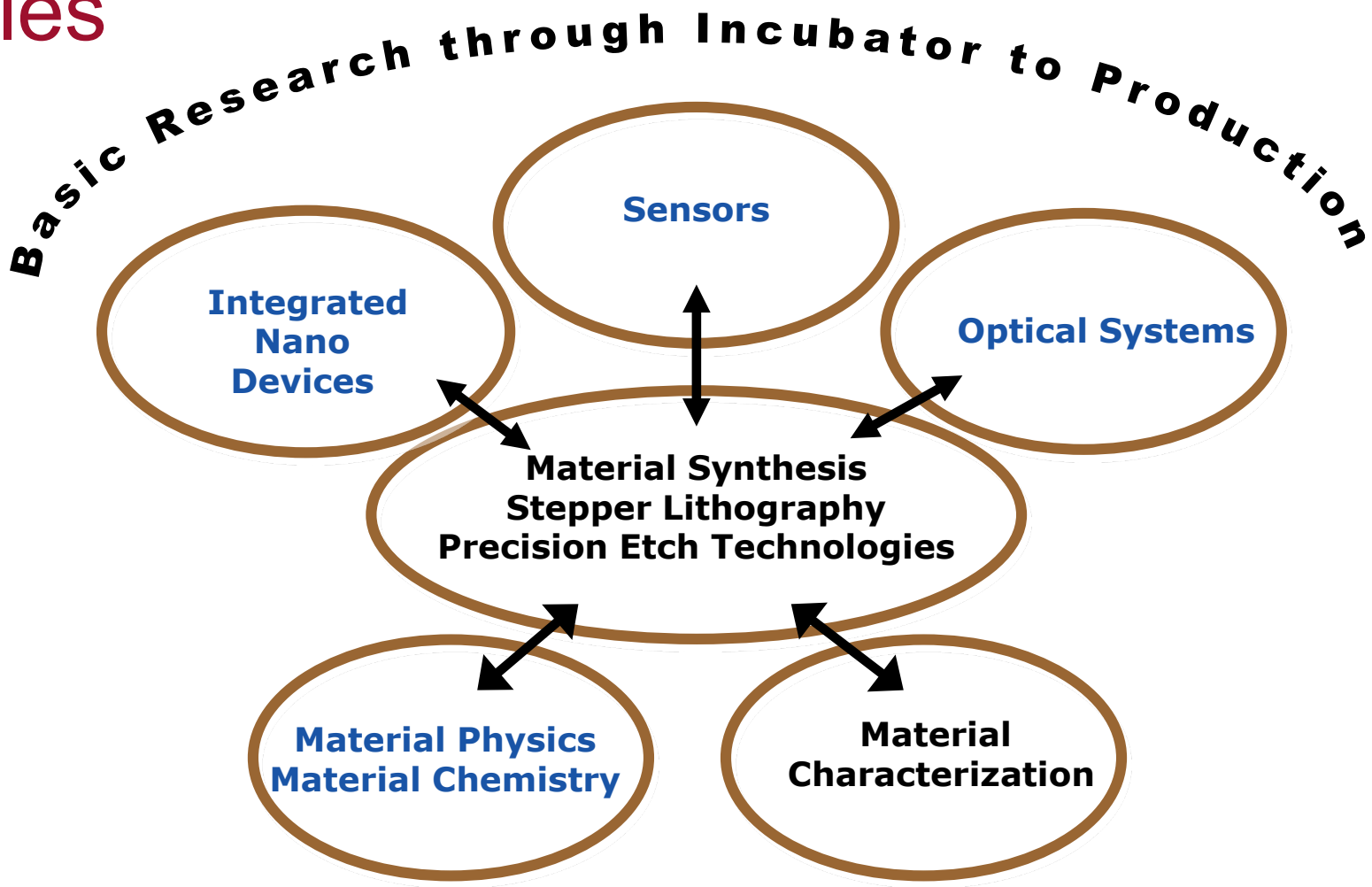
InP - Opto / electronics
GaAs - Opto / electronics
SiC - Electronics

Post process: dicing and bonding

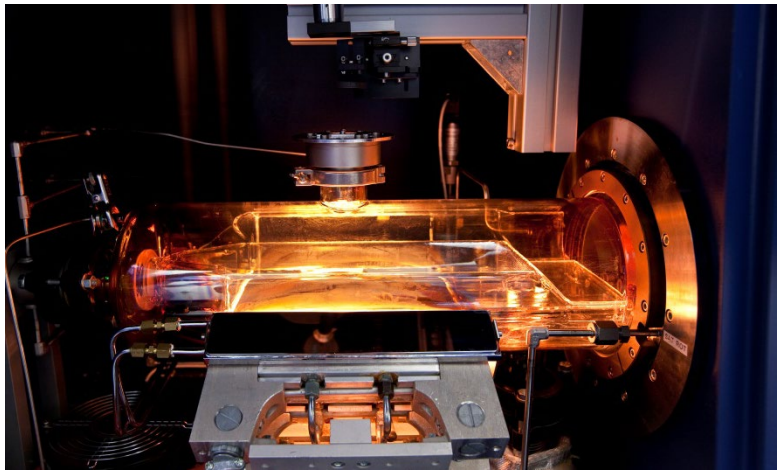
Characterization of materials and devices

Design and simulation

Profiles

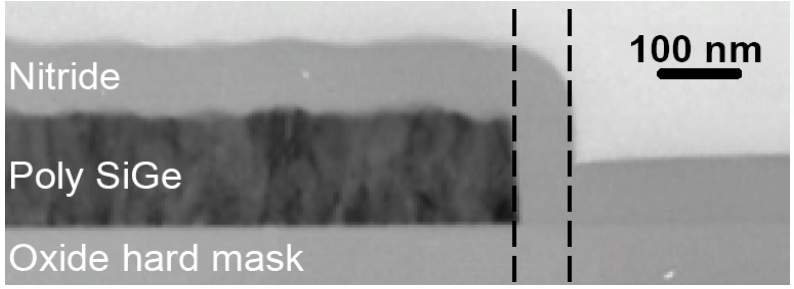

Basic Research through Incubator to Production
Sensors
Integrated Nano Devices
Optical Systems
Material Synthesis
Stepper Lithography
Precision Etch Technologies
Material Physics
Material Chemistry
Material Characterization

Material synthesis



- Vapor phase epitaxy of semiconductor materials
- Pulsed laser ablation of advanced oxides
- Atomic Layer Deposition of complex materials
- Magnetron sputtering of spintronic materials
- Wet chemistry for nanoparticles and nanostructured surfaces

Stepper Lithography



- i-line and g-line steppers
- Wafer sizes up to 200 mm
- Resolution down to 0.5 µm (i-line)
- Alignment accuracy: 60 nm (i-line)
- Throughput: up to 80 wafers/h

- Sidewall Transfer Lithography: Allows line widths down to 10 nm

Precision etch technologies

- Centura and P5000 etchers (Applied Materials)
- End point detection
- Wafer sizes up to 200 mm
- Chambers for etching of
  - Conventional Si structures
  - Deep Si structures
  - Metals
  - Dielectrics

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Material characterization

High resolution scanning electron microscopy
- environmental microscopy
- focused ion beam
- chemical analysis

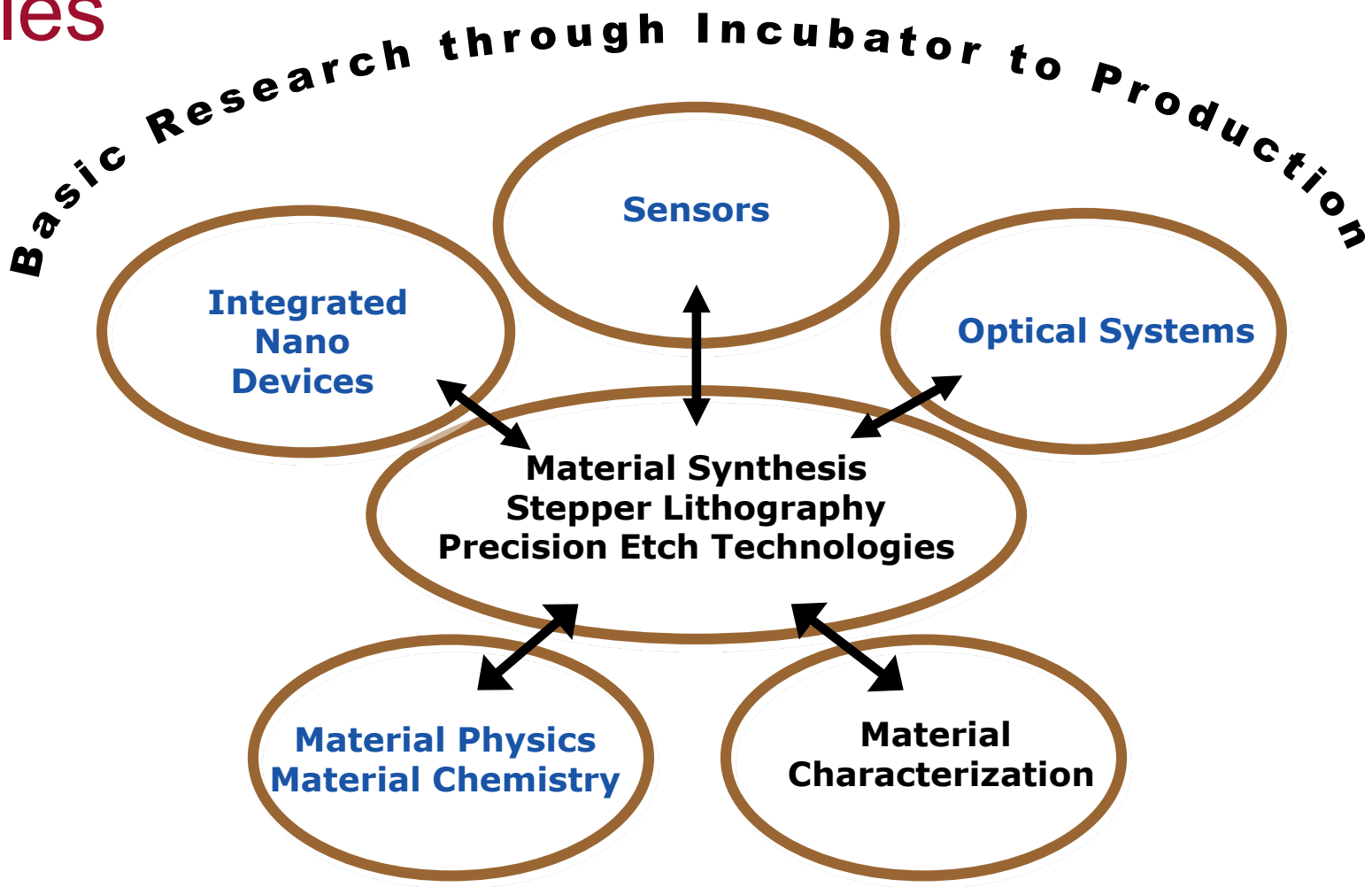
High resolution transmission electron microscopy
- with chemical analysis

Nano particle characterization

Scanning probe techniques

Electric, optic and magnetic characterization

Profiles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Material Characterization

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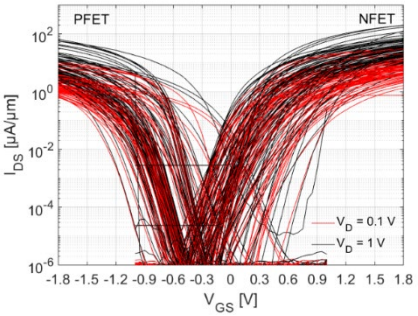
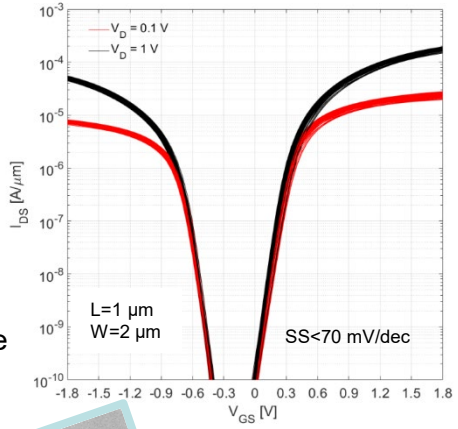
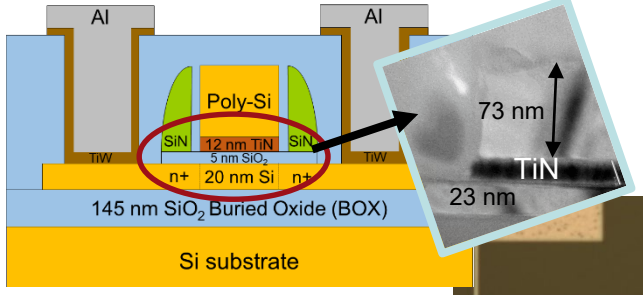
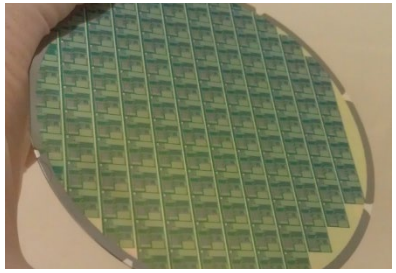
CMOS line for heterogeneous integration

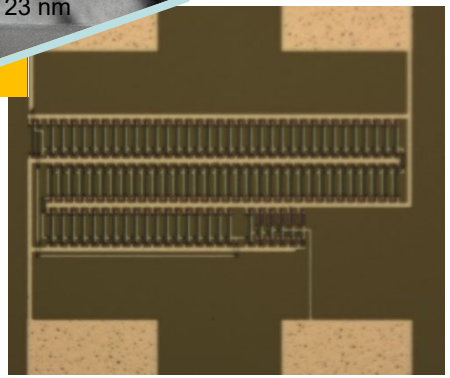




Transistor characteristics before and after process optimization







- CMOS circuits for integration:
  - Non-conventional devices: chemical sensors, biosensors, energy harvester, optical components…
  - Evaluation of new materials and designs
- A reproducible and predictable CMOS line
  - 100 mm wafers, 5 nm SiO_2 gate, 3 GHz operation
- Conservative design rules
  - i-line stepper: 0,5 µm resolution, 50 nm alignment
  - Active/metal: 2 µm, contact holes: 1x1 μm^2
- Simple circuits designs achieved:
  - Ring oscillator, inverter, frequency divider…
- Cadence Virtuoso design environment
- Available for collaboration projects

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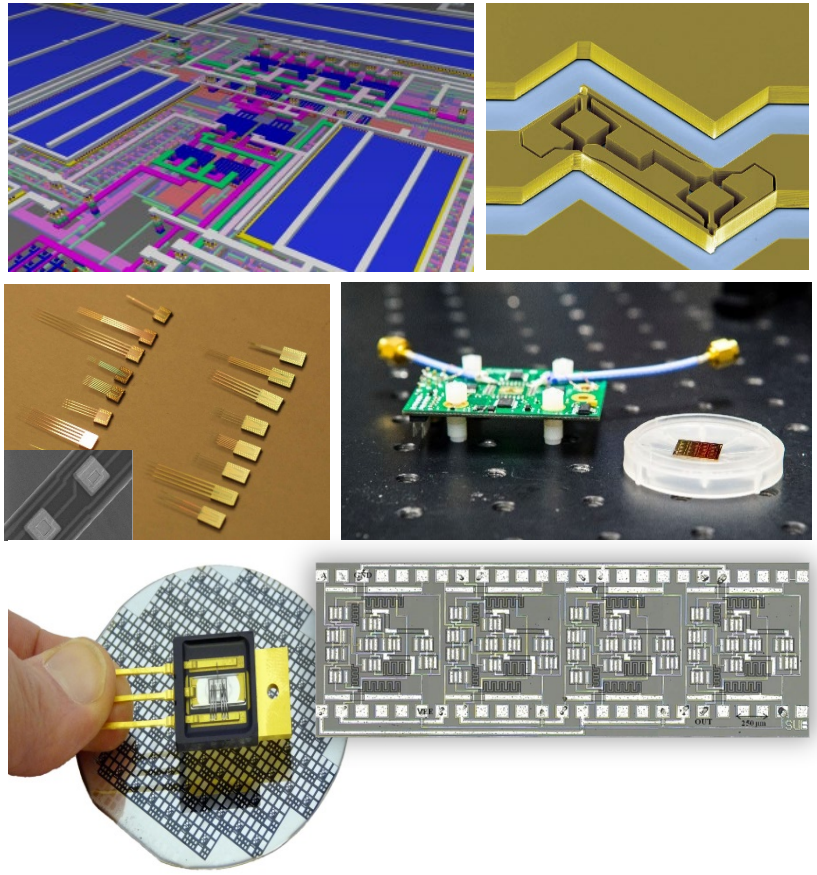
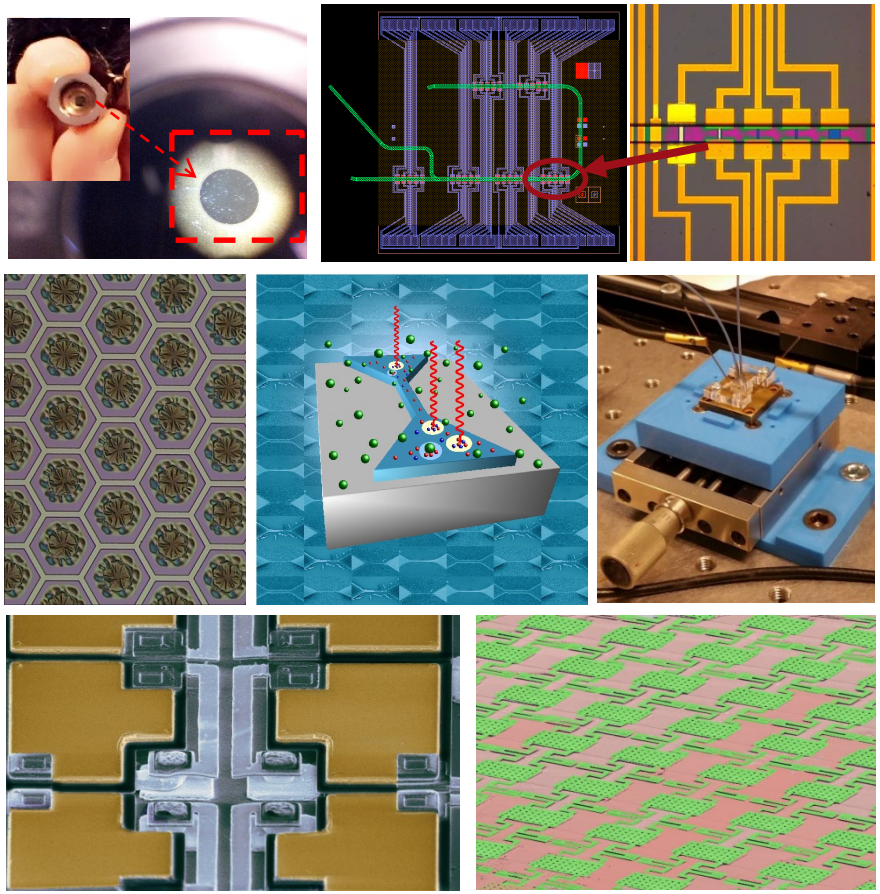
Integrated micro and nano devices



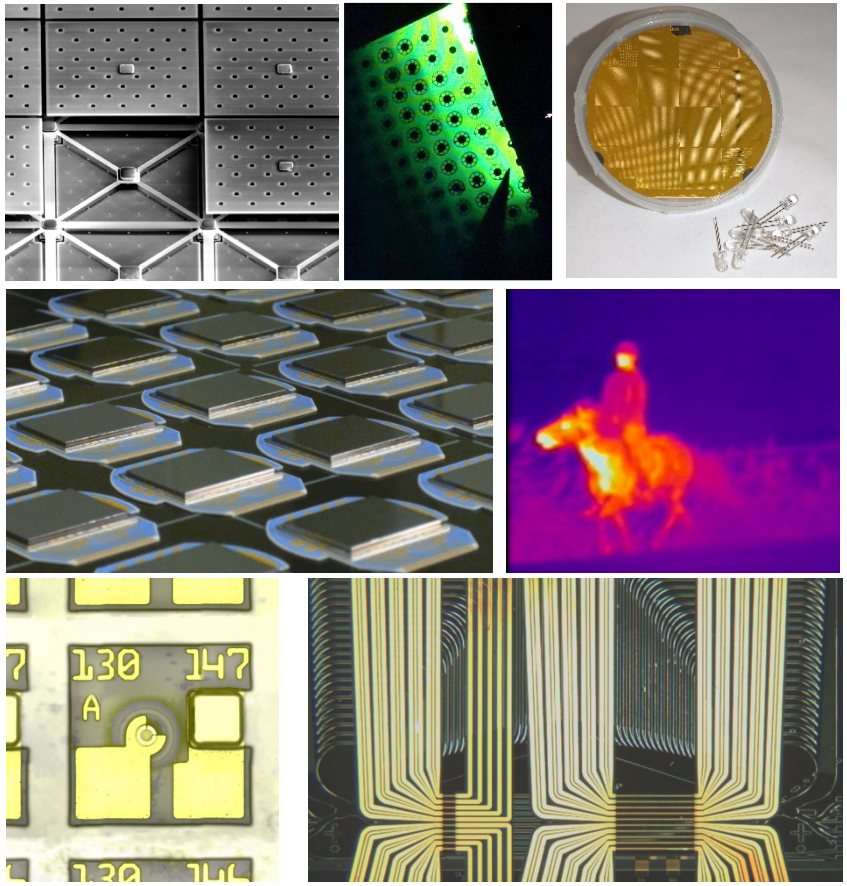
- Monolithic 3D Integration for silicon / silicon-germanium radio frequency integrated circuits
- High frequency micro mechanical switch for telecom
- Micro needles with multiple contacts for brain studies
- Quantum well electro-absorption modulators for Free-space optical communication
- Silicon carbide discrete power devices and integrated circuits for high power and high temperature applications
- Device design and characterization

Sensors



- Silicon carbide high pressure & high temp. sensors for automotive industry
- Micro fluidic chip for protein bio sensing
- Ferromagnetic filter for detection of electron spin polarization
- Silicon nano wires for protein detection
- Infrared detector – uncooled bolometer array for night vision systems in cars
- High impedance surface array for automotive radar

Optical systems



- Micro mirrors for light beam control
- Green LED with transparent graphene electrode
- Volume production of sensor arrays for IR cameras
- Vertical cavity surface emitting lasers for optical communication.
- Photonic integrated circuits for telecom

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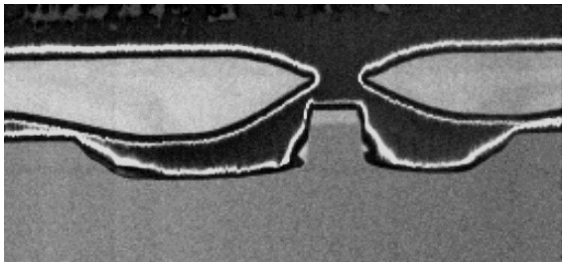
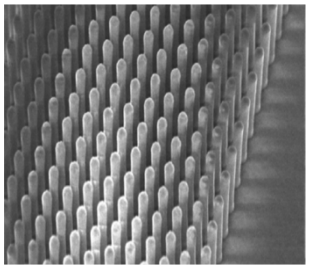
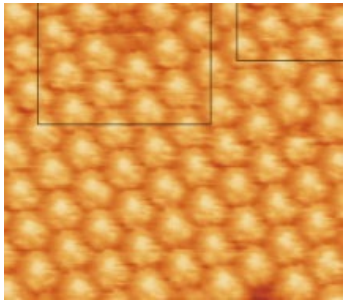
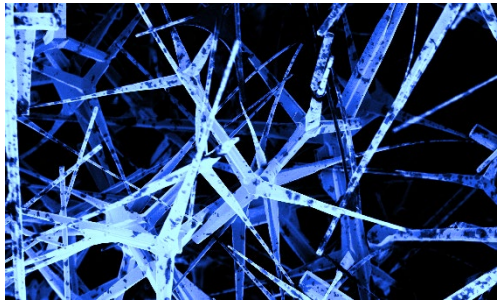
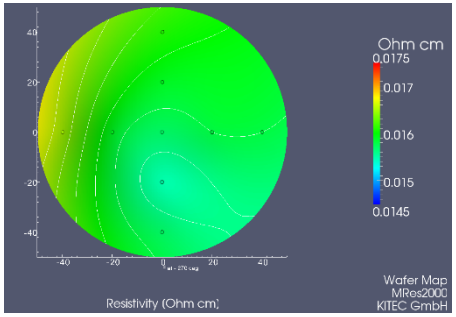
Material physics

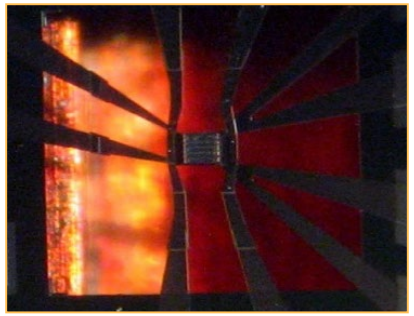












- Advanced crystal growth studies
- Photonic crystals
- Electronic and atomic structure of surfaces and interfaces
- Graphene and zink oxide for sensing in forensic and med tech applications
- Highly uniform and defect free SiC substrates
- Spintronic materials and devices
- Novel characterization techniques

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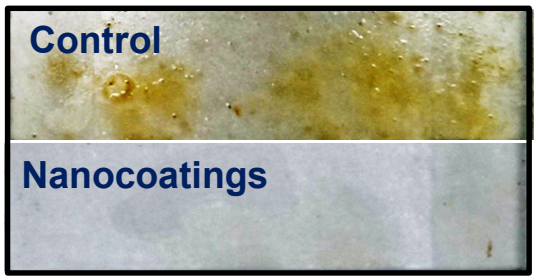
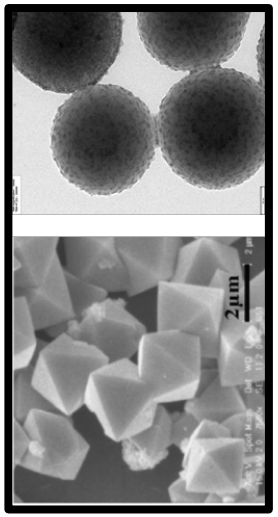
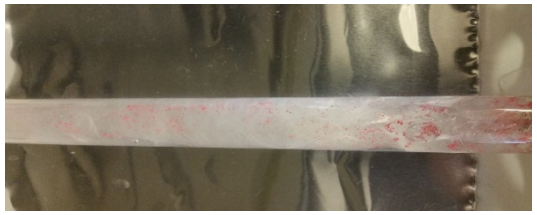
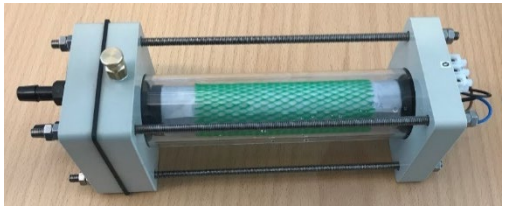
Functional Materials

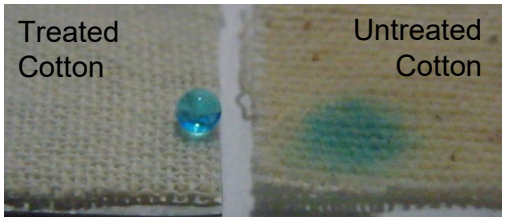








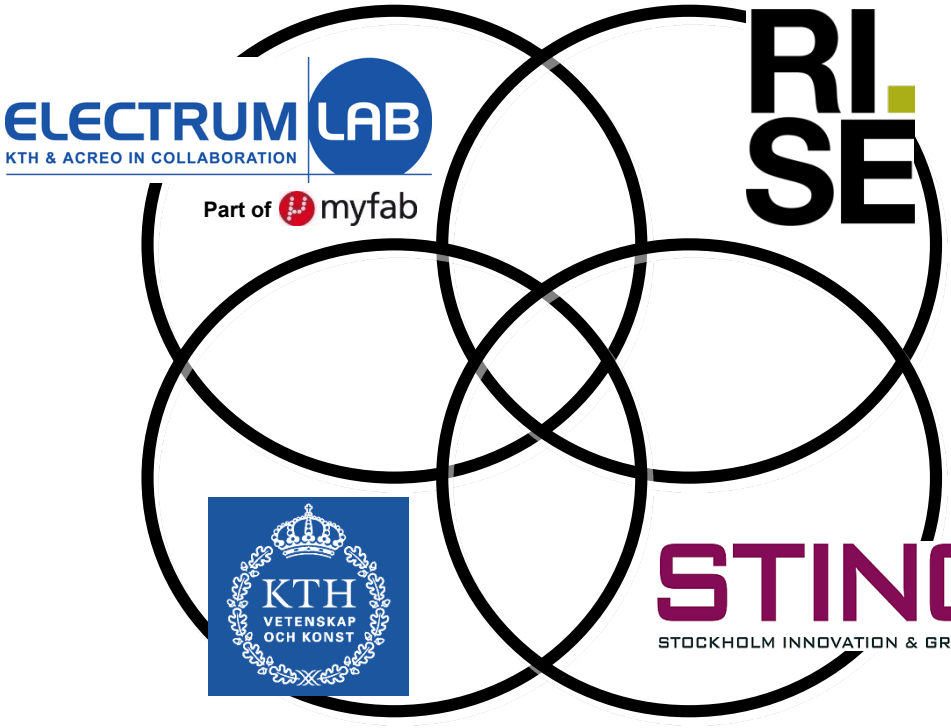
Photocatalysis



Nanoparticles and nanostructured surfaces

- Nano-coatings for environmental friendly anti-fouling treatment
- Investigations of micro plastics degradation
- Zink oxide nanorods for water purification
- Sea water low power desalination pilot plant (Värmdö)
- Zink oxide as photo catalyst forming antibacterial active surfaces
- Self cleaning surfaces

The Electrum Innovation System: Fosters Companies:



silex MICROSYSTEMS

ascilion
Pain-free glucose measurements

IRnova

ascatron

SCINT-X
STRUCTURED SCINTILLATORS

NanOsc

Kiselkarbid i Stockholm

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Incubator

Access to the whole lab:
- Processes
- Characterization
- Network of researchers and entrepreneurs

Proprietary lab area for rent:
- For own tools

Access to Myfab and ISSP partners:
- Backup processes
- Profile processes

Acreo production incubator:
- Technology transfer
- Technology and product development projects
- Foundry services

STING business incubator:
- Startup
- Business lab
- Business accelerator

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Success Factors
- Research into innovation

Ideas from research and development:
- In house (KTH or RISE Acreo) or external
- Making researchers to entrepreneurs: STING & RISE Acreo

Lab access:
- Flexibility - new ideas explored and developed
- Processing and characterization in existing tools
- Transparent price model

Facility support:
- Full support from the facility
- Authority Permits, chemical handling, etc.

Personnel resources:
- Training
- Processing & Characterization
- Network of people

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Success Factors

- Developing in incubator

Maturing technology:

- Manufacturability: RISE Acreo production incubator
- Market penetration: STING

Lab access:

- Refining processes
- Process stability for yield
- Access to partners: Backup & Profile processes
- Lab area for rent - proprietary & shared tools
- ➢ **Organize lab to always have empty space**

Facility support:

- Company may contribute to Electrum environment

Personnel resources:

- "Foundry services" in processing & characterization
- Network of people

External

KTH

RI. SE

Research into innovation → **Maturing in incubator** → **Full production** → **Move out to own production facility or foundry or stay**

ELECTRUM LAB
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Success Factors

- Ready to fly

Full production:
- Mature technology and sales organization
- Need full control of processes and costs

Lab access:
- Stable processes
- ISO 9001 certified management system
- Lab area for rent - proprietary & shared tools

Facility support:
- Company contributes, e.g., to safety arrangements

Personnel resources:
- Recruiting people in the lab environment

Moving out or stay?:
- Expensive to stay for high volumes
- Cost efficient to stay for low volumes in shared tools
- ➢ **Moving out creates a financial setback for the lab but frees space for next company to grow**

External

KTH

RI. SE

Research into innovation → **Maturing in incubator** → **Full production** → **Move out to own production facility or foundry or stay**

ISO 9001:2015 certified management system

Defines:

- Overall organization and roles
- Work routines and safety
- Information flow and meetings
- Tool maintenance and uptime
- Process, monitoring and reproducibility
- Characterization tool calibration
- Education of personnel and lab users
- Customer handling
- Yearly user poll
- Yearly audits and continuous follow-up

As part of KTH, also certified according to the environmental management standard ISO14001:2015

DNV·GL

MANAGEMENT SYSTEM CERTIFICATE

Certificate No: 114402-2012-AQ-SWE-SWEDAC
Initial certification date: 10, April, 2012
Valid: 10, April, 2018 - 10, April, 2021

This is to certify that the management system of

KTH - Electrum Laboratory
Isafjordsgatan 22, 164 40, KISTA, Sweden

has been found to conform to the Quality Management System standard:
ISO 9001:2015

This certificate is valid for the following scope:
Provision of laboratory facilities for education, research, development and production, including both cleanroom with process lines for device research and manufacturing, and laboratories for synthesis and processing, materials and device characterization, and die mounting.
Supporting technologies such as micro and nano electromechanical systems, micro- and nanoscale materials, electronic and photonic components for devices in silicon and in compound semiconductor materials and for materials research.

Place and date:
Solna, 19, March, 2018

SWEDAC ACKREDITERING
Accred. no.1053
Certification of Management Systems
ISO/IEC 17021-1

For the issuing office:
DNV GL - Business Assurance
Box 6046/Hemvärnsgatan 9, 171 06, Solna, Sweden

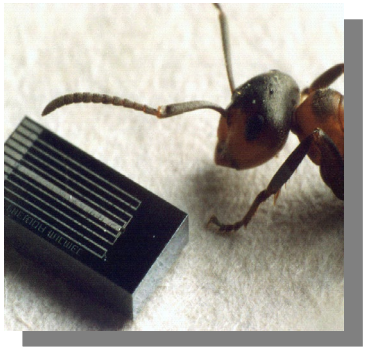
Ann-Louise Pått
Management Representative

Lack of fulfilment of conditions as set out in the Certification Agreement may render this Certificate invalid.
ACCREDITED UNIT: DNV GL Business Assurance Sweden AB, Box 6046, 171 06 Solna, Sweden. TEL:+46 8 587 940 00. http://assurance.dnvgl.com

From research to company I

Originated as a MEMS PhD project at KTH...

1994
KTH, RISE

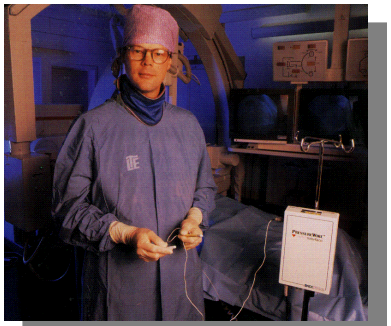


Microphone for turbulence research

1996
KTH, RISE, RADI

Miniaturised sensor for blood pressure measurements

1997
RADI, RISE



Clinical blood pressure measurements

2000
RADI, Silex, RISE

Production

2004
Silex

MEMS fab

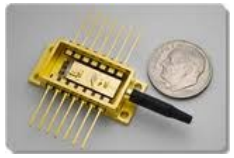
... Silex has developed to the world's leading "pure-play" MEMS foundry. In 2018:

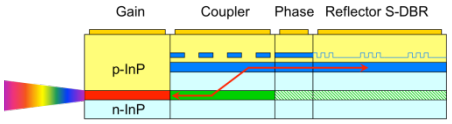
- turn-over 52 MEUR
- 180 employees

From research to company II

Advanced telecom laser research...

1987
RISE





Laser research for Swedish Telecom and Ericsson

1997
RISE, KTH, Altitun

Tunable telecom laser modules

ALTITUN

2000
Sold to ADC 872 MUSD

Production established in own fab, closed 2003.

2003
Syntune AB formed

Knowledge transfer and a foundry bought from Svedice in 2008.

2008
Ignis

2011
Finisar

Acquisitions by international companies

FINISAR

... has generated

- a great fortune for the owners
- revenue for the tax-payers
- employment for 150 persons
- turnover 26 MEUR (2019)

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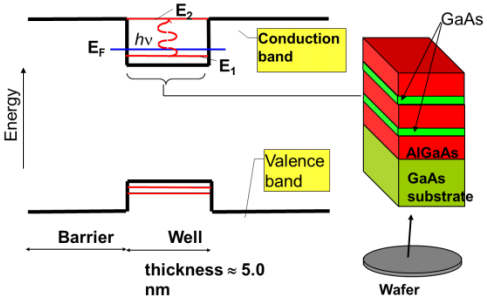
From research to company III

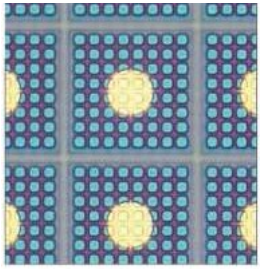
Quantum Well Infrared Photodetector (QWIP) structures developed...

1986
RISE



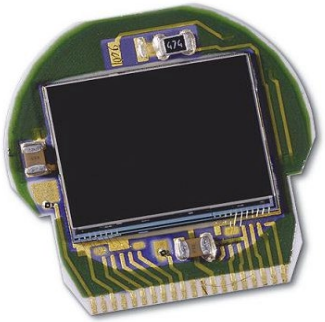
Quantum well structures formed by novel crystal growth technique

1991
RISE



Patent - grating for increased IR efficiency.

1997
RISE



Product launched - QWIP detector with read out circuit

2007
IRnova

Integrated modules with Stirling cooler

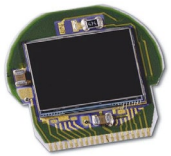
2012
IRnova

SF_6 gas detector

... into imaging IR detectors and modules at IRnova.
In 2018:

- turn-over 5 MEUR
- 28 employees

Incubator companies



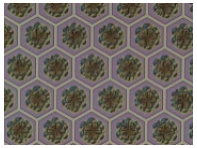
IR-Nova (2003)
Imaging IR detectors with high detectivity and resolution

TranSiC (2005) **- Fairchild** (2011) - **On Semiconductor** (2016)
High power transistors in silicon carbide

Ascatron AB (2011)
Pure play foundry for silicon carbide epitaxy and processing

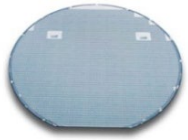
Spinn-Y AB (2011)
Spin filter for electron spin polarization detection

Kiselkarbid i Stockholm AB (2017)
Defect free silicon carbide substrates



Bright Day Prototypes (2017)
Development of sustainable energy solution

Nanosized AB (2018)
Nanoparticle size determination for semiconductor industry



Nano Pro AB (2018)
Consultancy and fabrication of semiconductor devices

Gatty Instruments AB (2018)
MEMS based gas sensors

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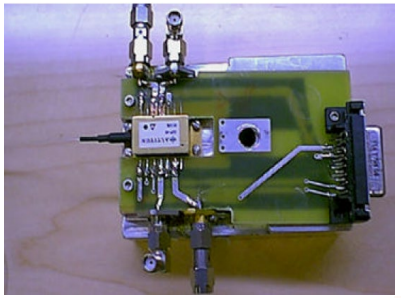
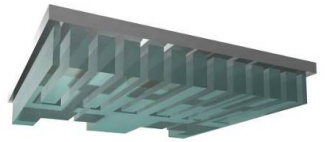
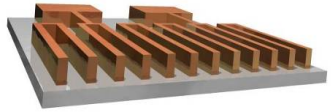
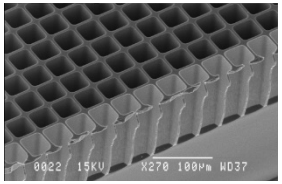
More start-ups

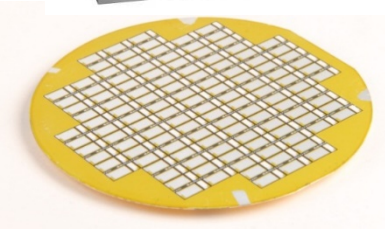
- **Altitun AB (1997)**
  - *Optoelectronics for telecommunication*
- **Optillion AB (1999)**
  - *Optoelectronics for telecommunication*
- **Silex Microsystems AB (2000)**
  - *Micromechanic devices for opto and bio applications*
- **Comlase NT AB (2001/2003)**
  - *Pump lasers and coating technologies*
- **Advanced Microwave Device Solutions AB (2001)**
  - *High power/high frequncy transistors in silicon carbide*
- **PhoXtal Communications AB (2002)**
  - *Optoelectronics for telecommunication*
- **Replisaurus Technologies AB (2002)**
  - *Electrochemical Pattern replication*
- **Scint-X AB (2006)**
  - *Imaging x-ray detector with high sensitivity and resolution*
- **Micro Delta T (2007)**
  - *Nanostructured surfaces for enhanced heat transfer*
- **NanOsc AB (2007)**
  - *Oscillators for telecommunication and other applications*
- **Nocilis Materials AB (2011)**
  - *Epitaxy of advanced Si-Ge-Sn-C alloys and energy harvesting*
- **Epiclarus AB (2012)**
  - *Epitaxial growth of III-V materials*
- **Ascilion AB (2012)**
  - *Pain-free glucose measurements*
- **Neosense AB (2014)**
  - *Sensor for real-time measurement of blood oxygenation*
- **Aninkco AB (2015)**
  - *Graphene based inks for printed electronics*











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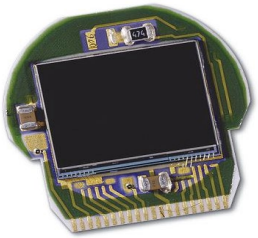
Success factors for innovation and growth

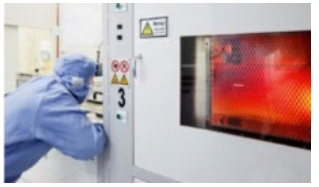
Technical: Handling the technical challenges
- Nanotechnology is demanding and every detail must work
- Management must understand the R&D realities
- Time could be more important than money

Financial: Financing of the project.
- The idea needs to mature - ”there is always money for good ideas”
- Working for free for some time - your own investment may attract others
- Financing is highly cyclical and may disappear quickly in a recession.

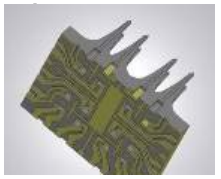
Market: For a nice idea to reach the market
- Early contacts with the market - help to develop the right thing
- Be open to adopt the technical solution to another application

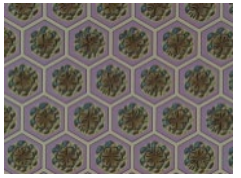
Team: A well formulated common goal
- Sort out the personal driving forces early


IR nova


Ascatron


TranSiC/ON Semi


Ascilion


Spinn-Y

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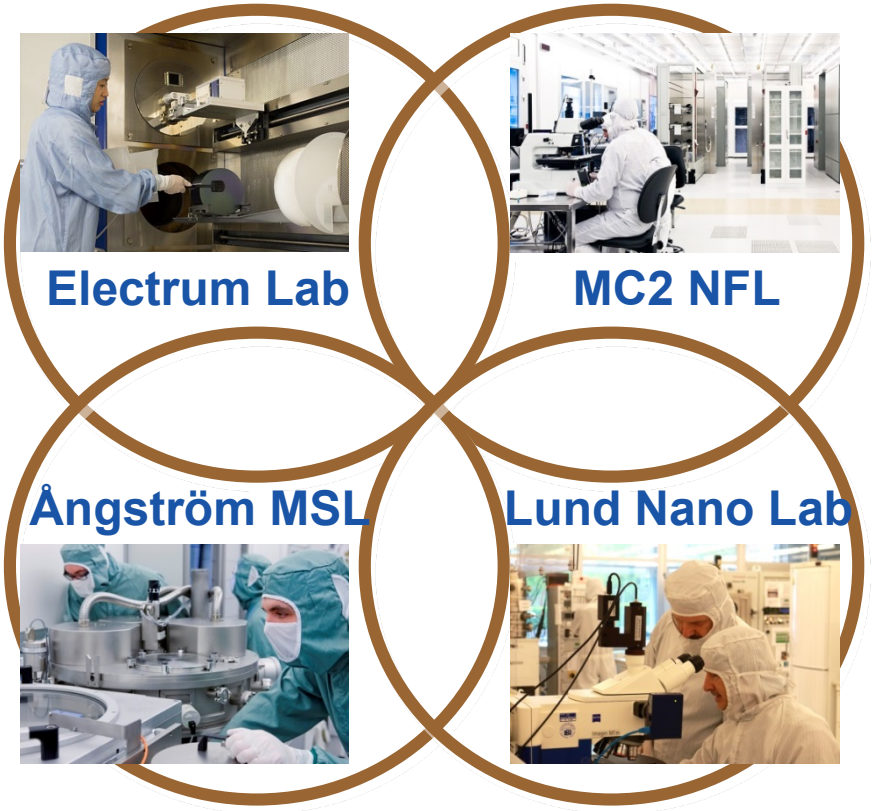
myfab Swedish Nano and Microfabrication Infrastructure



Realize your nano visions

- A distributed cleanroom facility
- Access to all processes and equipment in the network
- Backup for standard processes
- Supporting academia and industry
- Common marketing activities

Supported by

- Swedish Research Council (Vetenskapsrådet)
- The participating universities:
  - KTH
  - Uppsala University
  - Chalmers
  - Lund University

Contact for more information:
ulf.sodervall@chalmers.se
+46(0)31 772 34 31

Learn more at:

www.myfab.se

Myfab National Access offers **free** access to Myfab:

- Usage of equipment for fabrication and analysis
- Training services from on-site staff
- Scientific support in realizing “nano visions”
- Standard material (to some extent)

Myfab National Access is open for

- Swedish academic users with no previous cleanroom experience.

Myfab National Access will

- Promote the Myfab laboratories
- Lower the barrier to realize novel ideas in micro and nanofabrication
- Stimulate the creation of new activities and relations.

CAMART^2 - Excellence Centre of Advanced MAterial Research and Technology Transfer

- A Horizon 2020 Widespread project

Partners

- Institute of Solid State Physics, University of Latvia
- KTH Royal Institute of Technology
- RISE Acreo

Goal

- To enhance the innovation capabilities of ISSP UL
- Commercialization of research results at ISSP UL
- Synergy with industrial partners
- Strengthen nanotechnology and materials physics in the Baltic Sea region.

Implementation

- Business Plan: Science, Innovation, Education, Infrastructure, Outreach, Organization.
- Funding: 15 MEUR + 16 MEUR infrastructure (2017-2023)

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Electrum Laboratory invites you!

KTH and RISE Acreo in collaboration offer:

Processes – from separate process steps to full device process sequences.

Characterization – from single measurements to integrated analysis for deep understanding of complex structures

- Process and characterization services are provided by our skilled experts
- Commissioned research and development projects
- Prototyping and small scale production
- Access to our tools for your own personnel
- Cleanroom area and labs to rent
- Education in process technology, characterization and cleanroom infrastructure.
- Access to the lab resources at our collaboration partners within the Myfab network.


Thanks for
your attention!